

Amendments to the Claims:

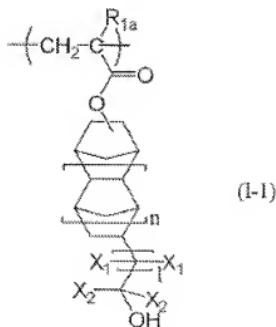
This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

1-12. (Cancel).

13. (Previously Presented) A radiation-sensitive resin composition comprising:

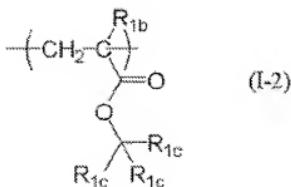
(A) a copolymer resin which comprises a recurring unit (I-1) shown by the following formula (I-1) and one or more other recurring units:



wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X₁ and X₂ individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator.

14. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (I-2) shown by the following formula (I-2):



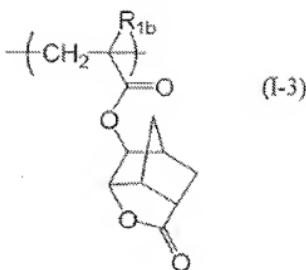
wherein R_{1b} represents a hydrogen atom or a methyl group, R_{1c} individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the R_{1c} groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the R_{1c} groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other R_{1c} group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms.

15. (Previously Presented) The radiation sensitive resin composition according to Claim 14, wherein the group -C(R_{1c})₃ in the formula (I-2) is an alkylcycloalkyl group.

16. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-80 mol% in 100 mol% of the total recurring units forming the resin.

17. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-50 mol% in 100 mol% of the total recurring units forming the resin.

18. (Previously Presented) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (1-3) shown by the following formula (I-3):



wherein R_{1b} represents a hydrogen atom or a methyl group.

19. (Previously Presented) The radiation-sensitive resin composition of Claim 13, further comprising (C) an acid diffusion controller.

20. (Previously Presented) The radiation-sensitive resin composition according to Claim 13, wherein in formula (I-1) n is 1, l is 1, each X_1 is H and each X_2 is CF_3 .

21. (New) The radiation-sensitive resin composition according to Claim 13, wherein the photoacid generator comprises at least one compound selected from the group consisting of 1-(4-n-butoxynaphthalen-1-yl)tetrahydrothiophenium nonafluoro-n-butanesulfonate and bis(4-t-butylphenyl)iodonium nonafluoro-n-butanesulfonate.